

Paul C Lemaire

List of Publications by Year in descending order

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#	ARTICLE	IF	CITATIONS
1	Facile Conversion of Hydroxy Double Salts to Metal-Organic Frameworks Using Metal Oxide Particles and Atomic Layer Deposition Thin-Film Templates. <i>Journal of the American Chemical Society</i> , 2015, 137, 13756-13759.	13.7	174
2	Conformal and highly adsorptive metal-organic framework thin films via layer-by-layer growth on ALD-coated fiber mats. <i>Journal of Materials Chemistry A</i> , 2015, 3, 1458-1464.	10.3	100
3	Highly Adsorptive, MOF-Functionalized Nonwoven Fiber Mats for Hazardous Gas Capture Enabled by Atomic Layer Deposition. <i>Advanced Materials Interfaces</i> , 2014, 1, 1400040.	3.7	99
4	Reversible Low-Temperature Metal Node Distortion during Atomic Layer Deposition of Al_2O_3 and TiO_2 on UiO-66- NH_2 Metal-Organic Framework Crystal Surfaces. <i>ACS Applied Materials & Interfaces</i> , 2017, 9, 22042-22054.	8.0	76
5	Using Hydrogen To Expand the Inherent Substrate Selectivity Window During Tungsten Atomic Layer Deposition. <i>Chemistry of Materials</i> , 2016, 28, 117-126.	6.7	62
6	Copper Benzenetricarboxylate Metal-Organic Framework Nucleation Mechanisms on Metal Oxide Powders and Thin Films formed by Atomic Layer Deposition. <i>ACS Applied Materials & Interfaces</i> , 2016, 8, 9514-9522.	8.0	60
7	Tungsten-Carbon Nanotube Composite Photonic Crystals as Thermally Stable Spectral-Selective Absorbers and Emitters for Thermophotovoltaics. <i>Advanced Energy Materials</i> , 2018, 8, 1801471.	19.5	57
8	Understanding inherent substrate selectivity during atomic layer deposition: Effect of surface preparation, hydroxyl density, and metal oxide composition on nucleation mechanisms during tungsten ALD. <i>Journal of Chemical Physics</i> , 2017, 146, 052811.	3.0	52
9	Thermal Selective Vapor Etching of TiO_2 : Chemical Vapor Etching via WF_6 and Self-Limiting Atomic Layer Etching Using WF_6 and BCl_3 . <i>Chemistry of Materials</i> , 2017, 29, 6653-6665.	6.7	35
10	Thermally Driven Self-Limiting Atomic Layer Etching of Metallic Tungsten Using WF_6 and O_2 . <i>ACS Applied Materials & Interfaces</i> , 2018, 10, 9147-9154.	8.0	32
11	Wafer-Scale Selective Area Deposition of Nanoscale Metal Oxide Features Using Vapor Saturation into Patterned Poly(methyl methacrylate) Templates. <i>Advanced Materials Interfaces</i> , 2016, 3, 1500431.	3.7	22
12	Insight into the removal and reapplication of small inhibitor molecules during area-selective atomic layer deposition of SiO_2 . <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2021, 39, .	2.1	15
13	Relation between Reactive Surface Sites and Precursor Choice for Area-Selective Atomic Layer Deposition Using Small Molecule Inhibitors. <i>Journal of Physical Chemistry C</i> , 2022, 126, 4845-4853.	3.1	15
14	Rapid visible color change and physical swelling during water exposure in triethanolamine-metalcone films formed by molecular layer deposition. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2016, 34, .	2.1	12
15	Metal-Organic Frameworks: Highly Adsorptive, MOF-Functionalized Nonwoven Fiber Mats for Hazardous Gas Capture Enabled by Atomic Layer Deposition (<i>Adv. Mater. Interfaces</i> 4/2014). <i>Advanced Materials Interfaces</i> , 2014, 1, .	3.7	5
16	Ab initio analysis of nucleation reactions during tungsten atomic layer deposition on Si(100) and W(110) substrates. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2018, 36, 061507.	2.1	4
17	Extending growth inhibition during area-selective atomic layer deposition of Al_2O_3 on aminosilane-functionalized SiO_2 . <i>Chemical Communications</i> , 2022, 58, 6650-6652.	4.1	1